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Supporting Information

Au nanoparticles induced localized surface plasmon resonance effect and synergistic catalytic sites in Au/Co₃O₄/Si pyramid arrays for photoelectrochemical hydrogen evolution

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Materials and Reagents

Silicon wafers measuring $10 \times 10 \text{ mm}^2$ were obtained from Zhejiang Huahe Silicon Material Co., Ltd. Chemicals such as sulfuric acid (H₂SO₄), hydrogen peroxide (H₂O₂), hydrofluoric acid (HF), potassium hydroxide (KOH), phosphorus oxychloride (POCl₄), ethylene glycol (EG), ethanol, and other reagents were purchased from Sinopharm Chemical Reagent Co., Ltd (Shanghai, China). Chemicals such as cobalt (II) nitrate hexahydrate (Co(NO₃)₂·6H₂O) and potassium auric chloride (KAuCl₄) were purchased from Aladdin Co., Ltd. Ultrapure water with a resistivity greater than 18.2 M Ω ·cm⁻¹ was used in this experiment. No further purification was performed on the compounds during the experiment.

Characterizations

Morphological observations of the material were performed on a Philips Tecnai G2 F30 S-TWIN high-resolution transmission electron microscope (HRTEM) and a HITACHI S-4800 field emission scanning electron microscopy (SEM), along with elemental mapping. X-ray diffraction (XRD) analysis was performed on a Bruker D8 X-ray diffractometer using Cu-K α radiation ($\lambda = 1.5406$ Å) with a scattering range of 10° to 80° for 20, at a scan rate of 2° min⁻¹. Raman spectra were measured on an In Via laser confocal Raman spectrometer in turn. X-ray photoelectron spectroscopy (XPS) measurements were measured on a Thermo Scientific X-ray photoelectron spectroscopy system (ESCALAB 250Xi) with monochromatic Al K α radiation (E = 1486.2 eV), and the binding energies were calibrated by C 1s to 284.8 eV. Oxygen vacancies were measured by electron paramagnetic resonance (EPR) (BRUKER EMXPLUS). The UV-vis diffuse reflectance spectrum was obtained on the Varian Cary 5000 UV-vis near-infrared spectrophotometer. Atomic force microscopy (AFM) tests were measured on a Bruker's icon and use contactless mode. The ICP-MS measurement was studied on Agilent 720ES. Details of the experiment are as follows:

First, the mass of the samples Si/Co₃O₄1/Au, Si/Co₃O₄5/Au, Si/Co₃O₄10/Au were weighed with an analytical balance (to the nearest 0.0001 g), and transferred to three clean sample digestion cups. Then, 3 mL of hydrochloric acid and 1 mL of nitric acid were added and left at room temperature for 30 min. The samples were then heated for degradation by an electric heating digestion apparatus with a pre-set ramp-up program, and finally the samples were continuously digested at 200 °C for about 60 min. After digestion was complete, the digestion cup was removed and cooled naturally to room temperature. Finally, the digestion solution was transferred and filtered into a 10 mL volumetric flask and the digestion vessel was rinsed three times, then volumed with deionized water to 10 mL, mixed well and left to be measured.

Standard curve:



Element concentration of the sample digestion solution was calculated as follows:

$$C_1 = C_0 \times f \tag{1}$$

where C_0 (mg L⁻¹) is the concentration of elements in the solution and derived from instrument testing. f is the dilution ratio.

The final result of the measured element was calculated as follow:

$$C_{\rm X} = \frac{C_1 \times V_0 \times 10^3}{m_0 \times 10^{-3}}$$
(2)

where m_0 (g) is the quality of the samples and recorded by analytical balance. V_0 (mL) is the volume of constant volume after sample digestion.

The final result of the measured element expressed as a percentage was calculated as follow:

$$W(\%) = \frac{C_x}{10^6} \times 100\%$$
(3)

Photoelectrochemical Measurements

The photoelectrochemical tests were conducted in a 0.5 M H_2SO_4 solution (pH = 0) on a CHI660D electrochemical workstation (Chenhua, Shanghai) with a three-electrode system consisting of the modified working electrode (WE), a saturated calomel electrode reference electrode (RE), and a graphite rod counter electrode (CE). The WE preparation method: Firstly, the oxide layer on the back of the silicon wafer is scraped with a blade and coated with a layer of Gallium/Indium eutectic alloy (\geq 99.99%, Sigma-Aldrich). Then, the copper wire with a diameter of 1 mm is linked to the back of the silicon wafer through conductive silver paste. Finally, the back and side of the electrode are wrapped with epoxy resin glue. The working area of the WE was controlled to 1 cm². A 100 mW·cm⁻² Xe light source (Perfect Light CHF-XM 500 coupled with an AM 1.5G filter) was used as a solar simulator. Linear sweep voltammograms (LSVs) measurements were conducted at a scan rate of 20 mV·s⁻¹. Electrochemical impedance spectra (EIS) measurements were carried out at frequencies from 0.1 Hz to 100 kHz under 0 V (vs. RHE) with an amplitude of 10 mV. All tests were performed without iR correction. The production of hydrogen was obtained by a GC9790II gas chromatograph (GC) at 0 V (vs. RHE) under simulated AM 1.5G solar irradiation.

Calculation of H₂

Standard curve:



According to the standard curve, the peak area measured in the experiment can be substituted to calculate the volume of H_2 produced by the reaction, and the amount of H_2 substance can be obtained by dividing the H_2 volume by 22.4 L·mol⁻¹. Hydrogen production rate can be obtained by dividing the amount of H_2 by the reaction time.

DFT theoretical calculations

Computational method

Calculations based on first-principles density functional theory (DFT), including molecular dynamics simulations were executed utilizing the Vienna Ab initio Simulation Package (VASP)¹ in conjunction with the Projector Augmented Wave (PAW) methodology². The exchange-correlation functional was managed within the parameters of the Generalized Gradient Approximation (GGA), adopting the Perdew-Burke-Ernzerhof (PBE) functional³. The geometric relaxation was carried through until the forces acting on each atom were less than 0.03 eV Å⁻¹. The sampling of the Brillouin zone was conducted using a 2*2*1 k-point grid. To assure rigorous consistency, calculations were performed until the energy convergence threshold was less than 10⁻⁵ eV. To effectively isolate periodic structures and preclude their interaction, a vacuum buffer of 15 Å was inserted along the z-axis. The unit cell is defined by the lattice constants: a = 16.09170 Å, b = 11.37860 Å, and c = 19.41550 Å. $\alpha = \beta = \gamma = 90^{\circ}$.

The free energy of the intermediates is calculated at zero potential and pH = 0,

$$\Delta G = \Delta E_{\rm DFT} + \Delta ZPE - T\Delta S \tag{4}$$

where ΔE_{DFT} , ΔZPE and ΔS are the changes of the reaction energy obtained from DFT calculations, zero-point energy, and the changes of entropy from the initial state to the final state, respectively. T is temperature and the T of 298.15 K was used in all computations.



Ra=94.8 nm



Ra=150 nm

Fig. S1 3D topographic AFM images showing surfaces of (a) Si/Co_3O_4 and (b) $Si/Co_3O_4/Au$.



Fig. S2 (a), (b) Cross-sectional SEM images of Si/Co₃O₄1. (c), (d) Cross-sectional SEM images of Si/Co₃O₄1/Au.



Fig. S3 (a), (b) Cross-sectional SEM images of Si/Co₃O₄10. (c), (d) Cross-sectional SEM images of Si/Co₃O₄10/Au.

	Ο	Si	Co	Au
and the second				
		<u>5 µm</u>	<u>5 μm</u>	<u>5 μm</u>

Fig. S4 EDX mapping image of the Si/Co₃O₄/Au.



Fig. S5 EDX spectrum of the $Si/Co_3O_4/Au$.



Fig. S6 (a) The electrochemical impedance spectra (EIS) raw data and fitted data of Si. (b) The EIS raw data of Si/Co₃O₄ and Si/Co₃O₄/Au with various electrodeposition times.



Fig. S7 ABPE curves of Si, Si/Co₃O₄, and Si/Co₃O₄/Au in 0.5 M H_2SO_4 under simulated AM 1.5G solar irradiation.



Fig. S8 UV–vis diffuse reflection of (a) Si/Co_3O_4 and (b) $Si/Co_3O_4/Au$ with various electrodeposition times.



Fig. S9 Structural modelling diagrams of (a) Co_3O_4 and (b) Co_3O_4 /Au.

Samples	Calibration volume (mL)	Au concentration of samples (wt%)
Si/Co ₃ O ₄ 1/Au	10	1.83
Si/Co ₃ O ₄ 5/Au	10	2.06
Si/Co ₃ O ₄ 10/Au	10	2.37

 Table S1. ICP-MS of Au concentration in different samples.

Catalyst	Electrolyte	Irradiance	Onset potential (V vs. RHE)	J (mA/cm²)	H ₂ evolution rate	ABPE (%)	Refs.
Si/Co ₃ O ₄ /Au	0.5 M H ₂ SO ₄	100 mW·cm ⁻² , AM 1.5 G	+0.42	-38.5@ 0 V _{RHE}	14.28 μmol min ⁻¹ cm ⁻²	3.7	This work
n ⁺ p-Si/Nb ₂ O ₅ /NiPt	0.5 M H ₂ SO ₄	100 mW·cm ⁻² , AM 1.5 G	+0.62	-32@ 0 V _{RHE}	130 μmol cm ⁻² in 5 h	5.2 @0.3 V _{RHE}	20234
Co-W-S/Ti/n ⁺ p-Si	1 M HClO ₄	100 mW·cm ⁻² , AM 1.5 G	+0.36	-30.4@ 0 V _{RHE}	/	4	20185
Si/rGO/MoS ₂	0.5 M H ₂ SO ₄	100 mW·cm ⁻² , AM 1.5 G	+0.38	-41.6@ 0 V _{RHE}	$18.1 \ \mu mol \ cm^{-2} \ min^{-1}$	3.4	20246
n ⁺ p- Si/Ti/WO ₃ @RuSe ₂	0.5 M H ₂ SO ₄	100 mW∙cm ⁻²	+0.54	-36@ 0 V _{RHE}	315 µmol in 3 h	9.43	20227
n ⁺ p-Si/Ti/Ru- MoS ₂	N ₂ - saturated 0.5 M H ₂ SO ₄	100 mW·cm ⁻² , AM 1.5 G	+0.53	-43@ 0 V _{RHE}	280 µmol in 160 min	7.28 (HC- STH)	20218
MoS ₂ /TiO ₂ /Si	0.5 M H ₂ SO ₄	100 mW·cm ⁻² , AM 1.5 G	+0.46	-33.7@ 0 V _{RHE}	$\begin{array}{c} 10.5 \ \mu mol \\ cm^{-2} \ min^{-1} \end{array}$	4.9	20219
Ni/TiO ₂ /a-Si/n-c- Si/a- Si/ITO/TiO ₂ /Pt	1 M HClO ₄ (pH=0)	AM 1.5 G	+0.62	-35@ 0 V _{RHE}	/	12.66	202010
Si/Co–NCNHP– TiO ₂ /CoP	0.5 M H ₂ SO ₄	100 mW·cm ⁻² , AM 1.5 G	+0.409	-23.04@ 0 V _{RHE}	550 μ mol cm ⁻² in 2 h	2.262	202411
Ni _{0.95} Pt _{0.05} Si/p-Si	0.5 M H ₂ SO ₄	100 mW·cm ⁻² , AM 1.5 G	+0.45	-40.5@ 0 V _{RHE}	/	5.3	202312
p-Si/In ₂ S ₃ /Pt	pH 5.7 phosphate buffer	AM 1.5 G	+0.5	-35@ -0.3 V _{RHE}	/	5.6 @0.25 V _{RHE}	202413
SimPy/MoO _x	$\begin{array}{c} 0.5 \text{ M} \\ \text{Na}_2 \text{SO}_4 \\ \text{solution} \\ (\text{pH} \\ \text{adjusted to} \\ 1 \text{ with} \\ \text{H}_2 \text{SO}_4) \end{array}$	100 mW∙cm ⁻² , AM 1.5 G	/	-35@ -0.4 V _{RHE}	11 μmol cm ⁻² min ⁻¹	/	2017 ¹⁴
Pt/rGO/p-Si	0.5 M H ₂ SO ₄	100 mW·cm ⁻² , AM 1.5 G	+0.43	-30.3@ 0 V _{RHE}	3.8 mmol in 5 h	4.9	2022 ¹⁵
Si-MoS ₂			+0.25	-30@ 0 V _{RHE}	1.5 mmol in 3 h	/	
Si-MoSe ₂	0.5 M	100	+0.22	-26@ 0 V _{RHE}	0.6 mmol in 3 h	/	202116
Si–WS ₂	(pH=0)	mw·cm ⁻² , AM 1.5 G	+0.24	-23@ 0 V _{RHE}	1.2 mmol in 3 h	/	202110
Si–WSe ₂	-		+0.18	-22@ 0 V _{RHE}	1.1 mmol in 3 h	/	
SiNW_AuCQDs	0.5 M H ₂ SO ₄	100 mW∙cm ⁻²	/	-35.5@ -1.2 V _{RHE}	182.93 μmol·h ⁻¹	6.1	202017

Table S2. Summary of PEC performance of state-of-the-art p-Si photocathodes.

SiNW/AuNP/MoS ₂	0.5 M H ₂ SO ₄	300 W xenon lamp with an AM 1.5 filter	+0.179	-14 @-0.5 V _{RHE}	246 mmol g ⁻ ¹ h ⁻¹	/	202318
TiO ₂ /AuNR/SiNH HN	0.5 M H ₂ SO ₄	100 mW·cm ⁻² , AM 1.5 G	+0.32	-26.2 @-0.25 V _{RHE}	450 μmol·h ⁻	/	201919
MoO _x /p-Si	0.5 M H ₂ SO ₄	100 mW·cm ⁻² , AM 1.5 G	/	-30 @-0.5 V _{RHE}	53 μmol g ⁻¹ h ⁻¹	/	2019 ²⁰

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